

AMENDMENTS TO THE CLAIMSLISTING OF CLAIMS

1. (Currently amended) A stain-resist composition comprising:
a crosslinking agent comprising at least one polymer having ~~at least two hydroxyl-~~
terminated groups; and
a stain-resist agent comprising at least one polymer,
wherein said crosslinking agent covalently binds said stain-resist agent.
2. (Currently amended) The stain-resist composition, according to Claim 1, wherein said crosslinking agent is a polybutadiene ~~having at least two hydroxyl group.~~
3. (Canceled)
4. (Original) The stain-resist composition, according to Claim 2, wherein said polybutadiene is further functionalized with at least one epoxy group.
5. (Currently amended) ~~The~~ A stain-resist composition ~~comprising: of Claim 1~~
a crosslinking agent comprising at least one polymer having two hydroxyl-terminated
groups; and
a stain-resist agent comprising at least one polymer,
wherein said ~~hydroxyl-terminated crosslinking agent is~~ polybutadiene is grafted with maleic anhydride.
6. (Original) The stain-resist composition of Claim 1, wherein said crosslinking agent contains at least one vinyl group.
7. (Previously presented) The stain-resist composition of Claim 1, wherein said stain-resist agent is a polymer selected from the group consisting of polymethacrylic acid, hydrolyzed maleic anhydride copolymerized with at least one monomer, and mixtures thereof.
8. (Original) The stain-resist composition of Claim 7, wherein the number average molecular weight of said polymethacrylic acid is at least 300,000.
9. (Previously presented) The stain-resist composition, according to Claim 7, wherein said at least one monomer is selected from the group consisting of α -olefins and styrenes.
10. (Original) The stain-resist composition of Claim 9, wherein said alpha-olefin is octene.

11. (Previously presented) The stain-resist composition, according to Claim 7, wherein up to 70 mole % of said maleic anhydride may be replaced by a monomer selected from the group consisting of acrylic acid, methacrylic acid, itaconic acid, vinyl sulfonic acid, vinyl phosphonic acid, styrene sulfonic acid, alkyl (C₁₋₄), acrylate, alkyl (C₁₋₄) methacrylate, vinyl acetate, vinyl chloride, vinylidene chloride, vinyl sulfides, N-vinyl pyrrolidone, acrylonitrile, acrylamide, and mixtures thereof.
12. (Original) The stain-resist composition of Claim 1, wherein said stain-resist agent further comprises a sulfonated phenol-formaldehyde condensation product.
13. (Original) The stain-resist composition of Claim 1, further comprising a pH-adjusting agent.
14. (Original) The stain-resist composition of Claim 13, wherein said agent adjusts the pH to from about 1 to about 8.
15. (Current amended) The stain-resist composition of Claim ~~13~~ 14, wherein said agent adjusts the pH to from about 3 to about 4.
16. (Currently amended) A process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, the process comprising contacting said polyamide substrate with a stain-resist composition comprising:
 - a crosslinking agent comprising at least one polymer having ~~at least two hydroxyl-~~ terminated groups; and
 - a stain-resist agent comprising at least one polymer,
 - wherein said crosslinking agent covalently binds said stain-resist agent.
17. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said crosslinking agent is a polybutadiene ~~having at least two hydroxyl groups.~~
18. (Canceled).
19. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 17, wherein said polybutadiene is further functionalized with at least one epoxy group.
20. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said crosslinking agent contains at least one vinyl group.

21. (Currently amended) The A process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, ~~according to Claim 18~~ the process comprising contacting said polyamide substrate with a stain-resist composition comprising:
a crosslinking agent comprising at least one polymer having at least two hydroxyl groups; and
a stain-resist agent comprising at least one polymer,
wherein said crosslinking agent is a hydroxyl terminated polybutadiene is grafted with maleic anhydride.
22. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist agent is a polymer selected from the group consisting of polymethacrylic acid, and hydrolyzed maleic anhydride copolymerized with at least one monomer, and mixtures thereof.
23. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim ~~16~~ 22, wherein the number average molecular weight of said polymethacrylic acid is at least 300,000.
24. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 22, wherein said monomer is a compound selected from the group consisting of α -olefins, and styrenes.
25. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 24, wherein said alpha-olefin is octene.
26. (Previously presented) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 22, wherein up to 70 mole % of said maleic anhydride may be replaced by a monomer selected from the group consisting of acrylic acid, methacrylic acid, itaconic acid, vinyl sulfonic acid, vinyl phosphonic acid, styrene sulfonic acid, alkyl (C₁₋₄) acrylate, alkyl (C₁₋₄) methacrylate, vinyl acetate, vinyl chloride, vinylidene chloride, vinyl sulfides, N-vinyl pyrrolidone, acrylonitrile, acrylamide, and mixtures thereof.
27. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist composition further comprises a sulfonated phenol-formaldehyde condensation product..
28. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said stain-resist composition further comprising a pH-adjusting agent.

29. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 28, wherein said agent adjusts the pH to from about 1 to about 8.
30. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim ~~28~~ 29, wherein said agent adjusts the pH to from about 3 to about 4.
31. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, further comprising drying.
32. (Original) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 31, wherein said drying is carried out at temperature of from about 100° to about 190°C.
33. (Currently amended) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim ~~31~~ 32, wherein said drying is carried out at temperature of from about 130° to about 150°C.
34. – 38. (Canceled)
39. (New) The stain-resist composition of Claim 1, wherein said crosslinking agent is a polymer selected from the group consisting of polyether, polyether copolymer, polyester copolymer, and polyolefin.
40. (New) The process for imparting resistance to staining by coffee and/or acid dyes to a polyamide substrate, according to Claim 16, wherein said crosslinking agent is a polymer selected from the group consisting of polyether, polyether copolymer, polyester copolymer, and polyolefin.